

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	IS&R	L1	12353	(430/270.1,271.1,272.1,275.1,283.1,311,313,317,318,906,907,927).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2005/05/10 10:10
2	BRS	L2	78	1 and negative adj3 resist and sulfonamide and @pd<"20041022"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2005/05/10 10:11
3	BRS	L3	29	430/283.1.ccls. and negative adj3 resist and @pd<"20041022"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2005/05/10 10:12
4	BRS	L4	14	"430"/\$.ccls. and resist and (fluorosulfonamide (fluorinated fluorination) near3 sulfonamide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	2005/05/10 11:01

	Type	L #	Hits	Search Text	DBs	Time Stamp
5	BRS	L5	19	"430"/\$.ccls. and (resist photoresist) and (fluorosulfonamide (fluorinated fluorination) near3 sulfonamide)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 10:55
6	BRS	L7	5	5 not 4	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 10:55
7	BRS	L8	48	"430"/\$.ccls. and (photoresist resist) and (fluorine fluorinated fluorination) same (sulfonated adj amide sulfonamide)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 11:03
8	BRS	L9	29	8 not (2 3 5)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 11:03

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	IS&R	L1	2	("6420503").PN.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 15:37
2	BRS	L2	2	1 and (resist photoresist)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 15:39
3	BRS	L3	2	1 and (imaging lithograph\$ etch\$ photolithograph\$)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:13
4	IS&R	L4	14	((("6,165,678") or ("6,177,428") or ("6,235,849") or ("6,477,750") or ("6744705") or ("6,410,748") or ("6,420,503"))).PN. or (2002/0115017).CCL S.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:03

	Type	L #	Hits	Search Text	DBs	Time Stamp
5	IS&R	L5	14	((("6,165,678") or ("6,177,228") or ("6,235,849") or ("6,277,750") or ("6344305") or ("6,410,748") or ("6,420,503")) .PN. or (2002/0115017) .CCL S.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:04
6	BRS	L6	13	5 and (sulfonamide imaging lithograph\$ etch\$ photolithograph\$)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:19
7	BRS	L7	7	5 and (sulfonamide) and (imaging lithograph\$ etch\$ photolithograph\$)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:19
8	IS&R	L8	12353	(430/270.1,271.1,2 72.1,275.1,283.1,3 11,313,317,318,906 ,907,927) .CCLS.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:19

	Type	L #	Hits	Search Text	DBs	Time Stamp
9	BRS	L9	78	L8 and negative adj3 resist and sulfonamide and @pd<"20041022"	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:19
10	BRS	L10	29	430/283.1.ccls. and negative adj3 resist and @pd<"20041022"	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:19
11	BRS	L11	19	"430"/\$.ccls. and (resist photoresist) and (fluorosulfonamide (fluorinated fluorination) near3 sulfonamide)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:21
12	BRS	L12	48	"430"/\$.ccls. and (photoresist resist) and (fluorine fluorinated fluorination) same (sulfonated adj amide sulfonamide)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:19

	Type	L #	Hits	Search Text	DBs	Time Stamp
13	BRS	L13	29	L12 not (L9 L10 L11)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:22
14	BRS	L14	55	(resist photoresist lithograph\$ etch\$ photolithograph\$) and (fluorosulfonamide (fluorinated fluorination) near3 sulfonamide)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:24
15	BRS	L15	36	14 not (L9 L10 L11 15)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:24
16	BRS	L16	1381	(resist photoresist lithograph\$ etch\$ photolithograph\$) and (polymer copolymer) same sulfonamide	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:28

	Type	L #	Hits	Search Text	DBs	Time Stamp
17	BRS	L17	73	(resist photoresist lithograph\$ etch\$ photolithograph\$) and (fluorosulfonamide (fluorinated fluorination) with sulfonamide)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:24
18	BRS	L18	54	17 not (L9 L10 L11 15)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:29
19	BRS	L19	86	(resist photoresist lithograph\$ etch\$ photolithograph\$) and (polymer copolymer)with sulfonamide and ("525"/\$.ccls. "526"/\$.ccls.)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:29
20	BRS	L20	76	19 not (L9 L10 L11 15 18)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T	2005/05/10 16:29